



AccuZone -ZC2

Photomask Resist Strip/Clean System

Application – Ozone and Hot-DI Wet Strip and Clean System

In Brief: Ozone gas in combination with heated DI water provides an alternative photoresist removal and surface clean chemistry to traditional SPM-based methods. Atomic oxygen released on decomposition of O₃ into O₂ + O rapidly attacks organics (C-H bonds) and the reaction byproducts are hydrolyzed and dissolved in hot DI water



Partially-stripped plate



AccuZone-stripped plate

概要
Overview

プロセス
Process

システム
SYSTEM

その他
Other

Features and Benefits

Feature	Benefit
Ozone gas and DIW chemistry	<ul style="list-style-type: none"> • Sulfate-free processing for Resist Strip and Clean eliminates Sulfate-residue haze formation • Avoids neutralization/abatement of hazardous waste stream • Eliminate wet-chemical mixing and supply modules
Heated DIW	<ul style="list-style-type: none"> • Enhances reaction rate for faster strip, better particle removal
Integration	<ul style="list-style-type: none"> • Fully Compatible standard MTC module, plus separate (remote-sited) O₃ generator unit
Built-in ozone abatement	<ul style="list-style-type: none"> • In-line treatment of liquid and exhaust streams within sealed system enclosure